

REACTIONS WITH ESTERS, HALIDES, AND HALOGENOIDS. I.  
BIS-(TRIETHYLTIN) OXIDE AND SULFIDE

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*Received June 1, 1954*

In Group IV-regular there is a gradual increase in basicity from the nearly neutral carbon to the clearly basic tin; this order of increasing basicity depends on experimental results mainly in aqueous or non-aqueous solutions.

An exploratory publication on organogermanium esters established  $(\text{Et}_3\text{Ge})_2\text{O}$  as the most basic,  $(\text{Et}_2\text{GeO})_4$  as the next most basic and  $[(\text{EtGeO})_2\text{O}]_n$  as the least basic ethylgermanium oxide (1). This work suggested that bis-(trialkyltin) oxides would react with numerous acids weaker than acetic acid; recent researches at this Institute demonstrate the reaction of  $(\text{Et}_3\text{Sn})_2\text{O}$  with  $\text{H}_2\text{S}$  or  $\text{C}_2\text{H}_5\text{SH}$  (2), or with  $\text{HCN}$  (3).

This present paper, exploratory in nature, clearly demonstrates the capture of halogen, halogenoid, or an ester group by tin at the expense of silicon, germanium, phosphorus, arsenic, or antimony. It also shows the transfer of halogen from tin of a higher oxidation number to tin of a lower oxidation number.

The basicity of organotin oxides decreases progressively as the oxygen content increases  $\text{Et}_4\text{Sn} > (\text{Et}_3\text{Sn})_2\text{O} > (\text{Et}_2\text{SnO})_n > [(\text{EtSnO})_2\text{O}]_n > \text{SnO}_2$ . Tin in the lowest oxidation number holds chlorine most firmly, while tin in the highest oxidation number holds chlorine least firmly:  $\text{Et}_3\text{SnCl}$ , oxidation number 1, holds halogen more firmly than  $\text{Et}_2\text{SnCl}_2$ , of oxidation number 2, which in turn holds halogen more firmly than  $\text{EtSnCl}_3$ , of oxidation number 3, which in turn holds halogen more firmly than  $\text{SnCl}_4$ , of oxidation number 4.

*Table I lists no new compounds*; there is good agreement between physical properties of the organotin products obtained and the published physical properties of the compounds—as shown in the experimental section.

Comparison of Table I and other experiments reported outside the Table shows that  $(\text{Et}_3\text{Sn})_2\text{O}$  is a more reactive base than either  $(\text{Et}_3\text{Sn})_2\text{S}$  or  $\text{Et}_3\text{SnSMe}$ , as might be expected. In Table I the organotin oxide reacts with  $\text{Me}_3\text{SiOCOMe}$ ,  $\text{Et}_3\text{Si}(\text{CN})$ , or  $\text{Me}_3\text{SiNCs}$ , while  $(\text{Et}_3\text{Sn})_2\text{S}$  reacts with none of these. Also,  $(\text{Et}_3\text{Sn})_2\text{O}$  reacts easily and rather completely with  $\text{Me}_3\text{SiOCOMe}$ ,  $\text{MeSi}(\text{OCOFCF}_3)_3$  and  $\text{Ph}_2\text{SiF}_2$ , while  $\text{Et}_3\text{SnSMe}$  reacts partially with the esters and not at all with the fluoride.

Upon consideration of the boiling points of the compounds, it is quite obvious that these reactions do not depend on the escape of the most volatile compound from the system under careful distillation, as in an earlier paper (4).

## EXPERIMENTAL

*Equipment* consisted of fully-interchangeable distilling units and receivers with 10/30 standard taper ground joints, including thermometers; a drying tube with  $\text{CaCl}_2$  excluded moisture from the system. Distillations usually were under reduced pressure in the leak-proof systems.

TABLE I  
 REACTIONS OF BIS-(TRIETHYL TIN) OXIDE AND SULFIDE

Starting Materials				Reaction Products					
Compound	Wt., g.	Compound	Wt., g.	Compound	Compound	Wt., g.	B.p., °C.	$n_D^{20}$	Yield, %
EtOBCl <sub>2</sub>	2.5	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.57	(EtOBO) <sub>n</sub>	Et <sub>3</sub> SnCl	0.65	206 <sup>b</sup>	1.507	37
EtOCOMe	2.30	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.40	EtOEt <sup>a</sup>	Et <sub>3</sub> SnOCOMe	1.60	—	—	92
EtOCOPh	1.00	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.55	EtOEt <sup>a</sup>	Et <sub>3</sub> SnOCOPh	0.85	124 <sup>c</sup>	—	36
Me <sub>2</sub> Si(OCCOF <sub>2</sub> ) <sub>2</sub>	0.68	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.40	(Me <sub>2</sub> SiO) <sub>n</sub> <sup>d</sup>	Et <sub>3</sub> SnOCOCF <sub>2</sub>	1.32	140 <sup>d</sup>	—	63
Me <sub>2</sub> SiOCOMe	1.28	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.50	(Me <sub>2</sub> Si) <sub>2</sub> O <sup>a</sup>	Et <sub>3</sub> SnOCOMe	1.90	214	—	98
MeOSi(NCO) <sub>2</sub>	.50	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.63	(MeOSiO) <sub>2</sub> O	Et <sub>3</sub> Sn(NCO)	1.73	160 <sup>e</sup>	—	90
Me <sub>2</sub> Si(NCS)	1.46	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.57	(Me <sub>2</sub> Si) <sub>2</sub> O	Et <sub>3</sub> Sn(NCS)	1.65	130 <sup>e</sup>	1.582	86
Et <sub>3</sub> Si(CN)	.3	(Et <sub>3</sub> Sn) <sub>2</sub> O	0.3	(Et <sub>3</sub> Si) <sub>2</sub> O	Et <sub>3</sub> Sn(CN)	.2	—	—	— <sup>f</sup>
MeSiCl <sub>3</sub>	1.30	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.25	(MeSiO) <sub>2</sub> O	Et <sub>3</sub> SnCl	1.10	208	1.506	77
SiBr <sub>4</sub>	.48	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.29	SiO <sub>2</sub>	Et <sub>3</sub> SnBr	1.57	221	1.531	91
DodSiI <sub>2</sub>	1.74	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.93	(DodSiO) <sub>2</sub> O	Et <sub>3</sub> SnI	2.64	234	1.564	88
Ph <sub>2</sub> SiF <sub>2</sub>	.2	(Et <sub>3</sub> Sn) <sub>2</sub> O	.2	(Ph <sub>2</sub> SiO) <sub>n</sub>	Et <sub>3</sub> SnF	—	—	—	— <sup>f</sup>
<i>n</i> -Pr <sub>2</sub> GeF	.22	(Et <sub>3</sub> Sn) <sub>2</sub> O	.40	( <i>n</i> -Pr <sub>2</sub> Ge) <sub>2</sub> O	Et <sub>3</sub> SnF	—	—	—	— <sup>f</sup>
<i>i</i> -Pr <sub>2</sub> GeOH	.3	(Et <sub>3</sub> Sn) <sub>2</sub> O	.3	( <i>i</i> -Pr <sub>2</sub> Ge) <sub>2</sub> O	Et <sub>3</sub> SnOH	.2	—	—	— <sup>f</sup>
GeCl <sub>4</sub>	.50	(Et <sub>3</sub> Sn) <sub>2</sub> O	2.00	GeO <sub>2</sub>	Et <sub>3</sub> SnCl	2.10	209	1.509	93
SnCl <sub>4</sub>	.76	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.54	SnO <sub>2</sub>	Et <sub>3</sub> SnCl	2.10	211	1.516	99
SnBr <sub>4</sub>	.68	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.35	SnO <sub>2</sub>	Et <sub>3</sub> SnBr	1.51	221	1.531	84
<i>n</i> -BuSnCl <sub>3</sub>	.82	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.87	( <i>n</i> -BuSnO) <sub>2</sub> O	Et <sub>3</sub> SnCl	1.95	210	1.508	92
SnCl <sub>2</sub>	.80	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.70	SnO	Et <sub>3</sub> SnCl	1.83	208	1.507	95
Et <sub>3</sub> SnCl <sub>2</sub>	1.10	(Et <sub>3</sub> Sn) <sub>2</sub> O	2.00	(Et <sub>3</sub> SnO) <sub>n</sub>	Et <sub>3</sub> SnCl	1.83	210	1.508	86
PCL <sub>3</sub>	.60	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.40	P <sub>2</sub> O <sub>5</sub>	Et <sub>3</sub> SnCl	1.15	207	1.509	74
AsCl <sub>3</sub>	.46	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.67	As <sub>2</sub> O <sub>3</sub>	Et <sub>3</sub> SnCl	1.66	208	1.507	88
SbCl <sub>3</sub>	.50	(Et <sub>3</sub> Sn) <sub>2</sub> O	1.40	Sb <sub>2</sub> O <sub>3</sub>	Et <sub>3</sub> SnCl	1.37	210	1.516	87
SiBr <sub>4</sub>	.70	(Et <sub>3</sub> Sn) <sub>2</sub> S	1.40	SiS <sub>2</sub>	Et <sub>3</sub> SnBr	1.60	218	1.529	88
DodSiI <sub>2</sub>	1.10	(Et <sub>3</sub> Sn) <sub>2</sub> S	1.08	(DodSiS) <sub>2</sub> S	Et <sub>3</sub> SnI	1.36	231	1.566	83
GeCl <sub>4</sub>	.45	(Et <sub>3</sub> Sn) <sub>2</sub> S	1.89	GeS <sub>2</sub>	Et <sub>3</sub> SnCl	1.84	208	1.508	91
SnCl <sub>4</sub>	.55	(Et <sub>3</sub> Sn) <sub>2</sub> S	1.86	SnS <sub>2</sub>	Et <sub>3</sub> SnCl	1.78	209	1.513	88
SnCl <sub>2</sub>	.67	(Et <sub>3</sub> Sn) <sub>2</sub> S	1.50	SnS	Et <sub>3</sub> SnCl	1.20	211	1.511	74
PCL <sub>3</sub>	.30	(Et <sub>3</sub> Sn) <sub>2</sub> S	1.45	P <sub>4</sub> Si <sub>10</sub> + P	Et <sub>3</sub> SnCl	1.43	210	1.510	92
AsCl <sub>3</sub>	.48	(Et <sub>3</sub> Sn) <sub>2</sub> S	1.75	As <sub>2</sub> S <sub>3</sub>	Et <sub>3</sub> SnCl	1.68	209	1.511	89

<sup>a</sup> Distilled before organotin product.

<sup>b</sup> M.p. 105–110°.

<sup>c</sup> One mm. pressure. M.p. of Et<sub>3</sub>SnOCOPh, 71°.

<sup>d</sup> M.p. 107–108°. 100 mm. pressure.

<sup>e</sup> M.p. 53°. 70 mm. pressure.

<sup>f</sup> Organotin compound crystallized out; no distillation performed.

Dod is *n*-C<sub>12</sub>H<sub>25</sub>. Ph is C<sub>6</sub>H<sub>5</sub>.

Typically, the *average run* consisted of weighing the distilling unit empty, then adding the GeCl<sub>4</sub> (for example) with reweighing to 0.01 g., and finally adding the (Et<sub>3</sub>Sn)<sub>2</sub>O (for example) in three or four portions until the calculated quantity was present. Solids such as SnCl<sub>2</sub> were always added first of all. In the reaction between GeCl<sub>4</sub> and (Et<sub>3</sub>Sn)<sub>2</sub>O 5–10 minutes of reflux at 760 mm. produced a large amount of solid GeO<sub>2</sub>; then the Et<sub>3</sub>SnCl was distilled at 129–134° under 67 mm. pressure. After reweighing the main distilling unit, the weight of the Et<sub>3</sub>SnCl was the same as the loss of weight of the system. Remeasurement in a test tube yield the accurate boiling point of the Et<sub>3</sub>SnCl.

Actual separations are best when the two reaction products are a readily volatile organotin compound (a pressure as low as one mm. is acceptable in distillation) and a non-volatile second compound; thus a reaction with MeSiCl<sub>3</sub> is preferable to one with Me<sub>2</sub>SiCl<sub>2</sub> or one with Me<sub>3</sub>SiCl.

Organosilicon impurities contaminated Et<sub>3</sub>SnOCOMe which boiled at only 214°. Mechanical trapping with EtOBCl<sub>2</sub> and an apparent azeotrope with ethyl benzoate produced low yields. A reaction between SnCl<sub>2</sub> and (Et<sub>3</sub>Sn)<sub>2</sub>S yielded SnS and Et<sub>3</sub>SnCl as expected,

but the SnS coated over the SnCl<sub>2</sub> and a two-hour distillation was necessary. In less than 30 minutes Et<sub>3</sub>SnF, Et<sub>3</sub>Sn(CN) or Et<sub>3</sub>SnOH crystallized from the appropriate reaction mixture almost without heating. After centrifugal separation the Et<sub>3</sub>SnOH melted at 43° and the acetate made therefrom melted at 118–119°. After a double recrystallization from CCl<sub>4</sub> the Et<sub>3</sub>Sn(CN) melted at 152–153°.

*Reactions not in Table I.* These show the limitations of the method. No reactions occurred in the following combinations: Et<sub>3</sub>SnSMe + Ph<sub>2</sub>SiF<sub>2</sub>; (Et<sub>3</sub>Sn)<sub>2</sub>S + Me<sub>3</sub>SiOCOMe; (Et<sub>3</sub>Sn)<sub>2</sub>S + Et<sub>3</sub>Si(CN); (Et<sub>3</sub>Sn)<sub>2</sub>S + Me<sub>3</sub>SiNCS. Five minutes reflux of 1.6 g. each of Me<sub>3</sub>SiOCOMe and Et<sub>3</sub>SnSMe, followed by standing overnight, yielded 0.7 g. of Et<sub>3</sub>SnOCOMe, m.p. 120° after drying in a vacuum; tin occurred in the supernatant liquid almost completely as Et<sub>3</sub>SnSMe. One g. of Et<sub>3</sub>SnSMe and 2 g. of MeSi(OCOCF<sub>3</sub>)<sub>3</sub> produced much Et<sub>3</sub>SnOCOCF<sub>3</sub>, which could be purified only by recrystallization. In a vigorous reaction (Et<sub>3</sub>Sn)<sub>2</sub>O and an equivalent quantity of PO(NCO)<sub>3</sub> yielded chiefly a non-volatile solid, probably (Et<sub>3</sub>Sn)<sub>3</sub>PO<sub>4</sub>; (Et<sub>3</sub>Sn)<sub>2</sub>O and an equivalent quantity of PO(NCS)<sub>3</sub> gave a product with *n*<sub>D</sub><sup>20</sup> 1.581, mainly Et<sub>3</sub>Sn(NCS). In a vigorous reaction of no preparative value, TiCl<sub>4</sub> and (Et<sub>3</sub>Sn)<sub>2</sub>O yielded lower halides of titanium. Reflux of HgCl<sub>2</sub> and (Et<sub>3</sub>Sn)<sub>2</sub>O produced a small amount of free mercury.

Test tubes served in the following reactions. Reaction of (Et<sub>3</sub>SnO)<sub>n</sub> with either SnCl<sub>2</sub> or SnCl<sub>4</sub> yielded Et<sub>2</sub>SnCl<sub>2</sub>, although neither reaction was complete. In one direction SnO and SnCl<sub>4</sub> yielded a product containing very little SnCl<sub>4</sub>; in the reverse direction SnCl<sub>2</sub> and SnO<sub>2</sub> furnished very little SnCl<sub>4</sub>. *n*-Butyltin trichloride reacted fairly well with SnO, reacted partially with (Et<sub>3</sub>SnO)<sub>n</sub>, and reacted not at all with SnO<sub>2</sub>.

*Physical properties of known tin compounds listed as products in Table I.* The chief properties follow, with refractive indices for white or for sodium D light. Et<sub>3</sub>SnF, m.p. 302° (5); Et<sub>3</sub>SnCl, b.p. 210°, m.p. 15°, *n*<sub>D</sub><sup>20</sup> 1.508 (5); Et<sub>3</sub>SnBr, b.p. 224°, m.p. -13°, *n*<sub>D</sub><sup>20</sup> 1.5821 (5); Et<sub>3</sub>SnI, b.p. 231°, m.p. -34°, *n*<sub>D</sub><sup>20</sup> 1.5648 (5); Et<sub>3</sub>Sn(NCO), b.p. 239°/760 mm. or 162°/80 mm., 48° (3); Et<sub>3</sub>Sn(NCS), b.p. 282° dec./760 mm. or 130°/1 mm., m.p. 33°, *n*<sub>D</sub><sup>20</sup> 1.583 on super-cooled liquid (3); Et<sub>3</sub>Sn(CN), b.p. 249° dec., m.p. 153° (3); Et<sub>3</sub>SnOH, m.p. 44–45° (5); Et<sub>3</sub>SnOCOMe, b.p. 224°, m.p. 119° (2, 3); Et<sub>3</sub>SnOCOCF<sub>3</sub>, b.p. 218°, m.p. 107° (2); Et<sub>3</sub>SnOCOPh, b.p. 132–134°/1 mm., m.p. 71° (2). *These published values are consistent with those listed in Table I.* In addition, qualitative tests showed the absence of sulfide in the liquid reaction products. Properties of the starting materials were usually unlike those of the products; (Et<sub>3</sub>Sn)<sub>2</sub>S has b.p. 303° dec., *n*<sub>D</sub><sup>20</sup> 1.5365 (2); (Et<sub>3</sub>Sn)<sub>2</sub>O, b.p. 272° (3, 5); Et<sub>3</sub>SnSMe, b.p. 224°, *n*<sub>D</sub><sup>20</sup> 1.529 (3).

As a whole, the preparative methods in Table I cannot compete with the traditional preparative methods.

*Starting materials.* *n*-Butyltin trichloride was available through the courtesy of Metal & Thermit Corp., New York, N. Y. Preparation of large amounts of (Et<sub>3</sub>Sn)<sub>2</sub>O and (Et<sub>3</sub>Sn)<sub>2</sub>S followed the published directions (2) or modifications thereof. Recent publications describe the preparation of Et<sub>3</sub>SnSMe (3), Me<sub>2</sub>Si(OCOCF<sub>3</sub>)<sub>2</sub> and MeSi(OCOCF<sub>3</sub>)<sub>3</sub> (6), MeOSi(NCO)<sub>3</sub> (7), Me<sub>3</sub>SiNCS (8), Et<sub>3</sub>Si(CN) (9), DodSiI<sub>3</sub> (10), *n*-Pr<sub>3</sub>GeF (11), and iso-Pr<sub>3</sub>GeOH (12).

*Related studies* are well under way; the oxide (Et<sub>3</sub>Ge)<sub>2</sub>O reacts in much the same manner as (Et<sub>3</sub>Sn)<sub>2</sub>O herein.

#### SUMMARY

Thirty successful reactions listed in Table I demonstrate the formation of a triethyltin ester, halide, or halogenoid through reaction of (Et<sub>3</sub>Sn)<sub>2</sub>O or (Et<sub>3</sub>Sn)<sub>2</sub>S with an ester, halide, or halogenoid of an element other than tin—or of tin in an oxidation number of 2, 3, or 4. Under gentle reflux without a solvent the average reaction is complete within 5 or 10 minutes and furnishes a yield of approximately 90%. An organotin halide forms at the expense of the less-basic silicon in the typical reactions SiBr<sub>4</sub> + 2 (Et<sub>3</sub>Sn)<sub>2</sub>O → SiO<sub>2</sub> + 4 Et<sub>3</sub>SnBr and

$\text{SiBr}_4 + 2 (\text{Et}_3\text{Sn})_2\text{S} \rightarrow \text{SiS}_2 + 4 \text{Et}_3\text{SnBr}$ . Halogen transfers easily from tin of oxidation number 2 in  $\text{Et}_2\text{SnCl}_2$ , 3 in  $n\text{-BuSnCl}_3$ , or 4 in  $\text{SnCl}_4$  to the more-basic tin of oxidation number 1 in the reactions  $(\text{Et}_3\text{Sn})_2\text{O} + \text{Et}_2\text{SnCl}_2 \rightarrow 2 \text{Et}_3\text{SnCl} + (\text{Et}_2\text{SnO})_n$ , also  $3 (\text{Et}_3\text{Sn})_2\text{O} + 2 n\text{-BuSnCl}_3 \rightarrow 6 \text{Et}_3\text{SnCl} + (n\text{-BuSnO})_2\text{O}$ , also  $2 (\text{Et}_3\text{Sn})_2\text{O} + \text{SnCl}_4 \rightarrow 4 \text{Et}_3\text{SnCl} + \text{SnO}_2$ . Basicity appears the decisive factor in all thirty successful reactions, which illustrate a method still little explored. A dozen reactions described outside the Table have no preparative value, and show some limitations of the method.

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